

<b>Notice of References Cited</b>	Application/Control No. 09/726,337	Applicant(s)/Patent Under Reexamination ZHANG ET AL.	
	Examiner W. David Coleman	Art Unit 2823	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
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**FOREIGN PATENT DOCUMENTS**

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	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Schoenfeld et al., "Crystallization of amorphous silicon by NiSi <sub>2</sub> precipitates" Thin Solid Films, vol. 261 pp 236-240, Elsevier 1995
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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